

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 61-035847  
(43)Date of publication of application : 20.02.1986

(51)Int.CI. B01J 19/08  
C23C 14/24  
C30B 23/00

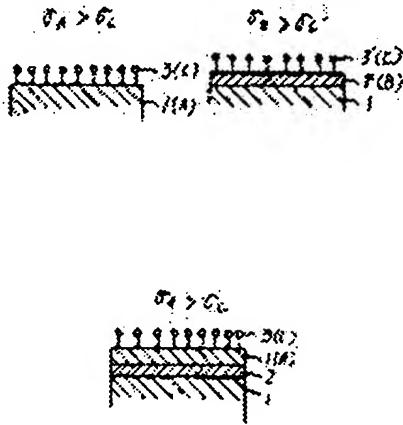
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## (54) PREPARATION OF MEMBRANE

### (57)Abstract:

**PURPOSE:** To form a controlled arbitrary atomic layer or molecular layer structure, in preparing the membrane utilized in an electronic device, by performing the growth of the membrane in the presence of an atomic group, wherein surface energy does not become larger than the energy of a growth surface, in the membrane growth surface.

**CONSTITUTION:** As third substances C, C', atomic groups or functional groups 3, 3' are chemical bonded to the atom of a growth surface or adsorbed thereby to make it possible to always keep the surface energies  $\sigma_C$ ,  $\sigma_{C'}$  of a formed membrane smaller than the energies  $\sigma_A$ ,  $\sigma_B$  of a substrate. Therefore, even through processes (a), (b), (c), all of films A, B can be always formed only of an arbitrary atomic layer as flat membranes. As a membrane forming stock material, a compound containing a membrane constituting element is pref. used and, as the stock compound, hydride, metal alkoxide or metal carboxide are pref.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]